

Amendments to the Specification:

Please replace the paragraph beginning at page 13, line 15, with the following amended paragraph:

Att-PSM **23** in FIG. 3b is tritone because it consists of three distinct types of regions which are the chrome blocking area **27** having a width W_3 that is greater than W_0 in FIG. 2b, clear transparent regions **25**, and attenuated regions **26** and **28** for the interconnect line and scattering bar, respectively. Interconnect Lines 26 and scattering bar 28 are both comprised of an attenuator material such as MoSiO_xN_y which has been deposited on the mask substrate. A less desirable option is to construct a binary mask where interconnect lines 26 and scattering bar 28 are chrome but a binary mask does not have the resolution or process window that is afforded by an att-PSM.